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(71) Applicant: **VERSUM MATERIALS US, LLC** [US/US];
8555 South River Parkway, Tempe, Arizona 85284 (US).

(72) Inventors: **CHEN, Chao-Hsiang**; c/o Versum Materials
US, LLC, 8555 South River Parkway, Tempe, Arizona
85284 (US). **GE, Jhih Kuei**; c/o Versum Materials US,
LLC, 8555 South River Parkway, Tempe, Arizona 85284
(US). **LEE, Yi-Chia**; c/o Versum Materials US, LLC, 8555
South River Parkway, Tempe, Arizona 85284 (US). **LIU,
Wen Dar**; c/o Versum Materials US, LLC, 8555 South Riv-
er Parkway, Tempe, Arizona 85284 (US).

(74) Agent: **SLAVEN IV, William T.**; c/o Versum Materials
US, LLC, 7350 Tilghman Street, Suite 104, Allentown,
Pennsylvania 18106-9000 (US).

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(54) Title: ETCHING SOLUTION FOR TITANIUM NITRIDE AND MOLYBDENUM CONDUCTIVE METAL LINES

(57) Abstract: Etching composition suitable for etching titanium nitride and molybdenum from a microelectronic device, which includes, consists essentially of, or consists of, in effective amounts: water; HNO₃; optionally, at least one chloride ion source selected from the group of NH₄Cl and HCl; a base selected from the group of an alkanolamine, NH₄OH, a quaternary ammonium hydroxide, and mixtures thereof; optionally, at least one fluoride ion source; optionally, at least one heteroaromatic compound; and optionally, at least one water-miscible solvent selected from the group of diethylene glycol butyl ether, sulfolane, and propylene carbonate.

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